

Erratum: “Quasiparticle electronic structure of phthalocyanine:TMD interfaces from first-principles *GW*” [J. Chem. Phys. 155, 214702 (2021)]

Gyanu P. Kafle and Zhen-Fei Liu^{a)}

Department of Chemistry, Wayne State University, Detroit, Michigan 48202 USA

(Dated: 27 July 2024)

In a subsequent investigation, we have found an error in our previously reported¹ *GW* electronic structure of the H₂Pc:MoS₂ interface when the composite system is supported on a SiO₂ substrate.

The correct line in Table I should be:

TABLE I. Key descriptors of the electronic structure for the H₂Pc:MoS₂ interface adsorbed on SiO₂ using *GW*. All values are in eV. Δ_{TMD}^0 and Δ_{mol}^0 are the band gaps of the freestanding TMD monolayer and molecular layer, respectively. Δ_{TMD}^0 is calculated at the *K* point for the unit cell, and Δ_{mol}^0 is calculated at the Γ point. Δ_{TMD} , Δ_{LL} , Δ_{HL} , Δ_{HH} , and Δ_{mol} are energy level differences within the interface systems defined in Fig. 2 of the original paper, all calculated at the Γ point.

	Interface	Method	Type	Δ_{TMD}^0	Δ_{TMD}	Δ_{LL}	Δ_{HL}	Δ_{HH}	Δ_{mol}	Δ_{mol}^0
Originally reported in Ref. 1	H ₂ Pc:MoS ₂ :SiO ₂	<i>GW</i>	IIa, Fig. 2(c)	2.81	2.07	0.68	1.62	0.45	2.30	3.86
Corrected result	H ₂ Pc:MoS ₂ :SiO ₂	<i>GW</i>	IIa, Fig. 2(c)	2.81	2.70	0.13	2.25	0.45	2.38	3.86

Correspondingly, the correct Fig. 4 of the paper should be:

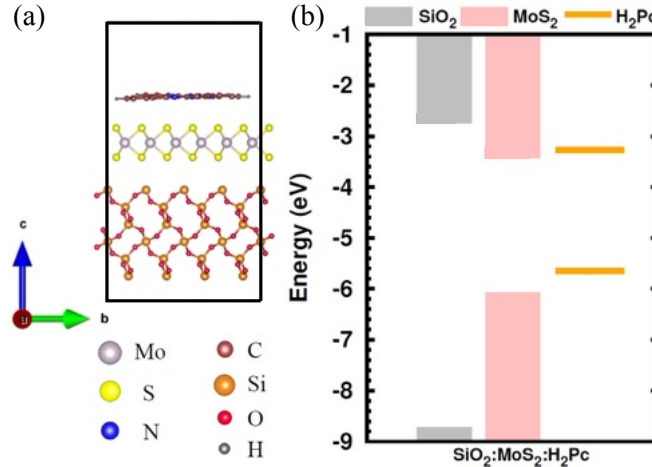


FIG. 4. (a) (This panel stays the same as in Ref. 1) Optimized structure of the H₂Pc:MoS₂:SiO₂ interface. (b) (This panel is corrected in this erratum) Quasiparticle energy level alignment from an embedding *GW* calculation, where the H₂Pc:MoS₂ interface is embedded into a dielectric environment of a SiO₂ substrate. All energy levels are measured with respect to vacuum.

Consequently, the substrate effect of SiO₂ is not as strong as we originally determined. Compared to the H₂Pc:MoS₂ interface, the SiO₂ substrate has a moderate effect of renormalizing the MoS₂ gap by about 0.08 eV. Due to the dielectric screening of SiO₂, the gap of H₂Pc within the H₂Pc:MoS₂ interface is renormalized by 0.09 eV, and the gap of the H₂Pc:MoS₂ interface is renormalized by 0.08 eV. The Δ_{LL} and Δ_{HH} in the H₂Pc:MoS₂ interface are nearly not affected by the SiO₂ substrate. This moderate screening effect of the SiO₂ substrate is consistent with Refs. 2–4, where the change in the band gap of MoS₂ is found to be in the 0.09–0.25 eV range when monolayer MoS₂ (without an H₂Pc molecule) is deposited on SiO₂ substrate.

This erratum does not alter the results of all other calculations without the SiO₂ substrate or the structure-property relationship that we predicted using *GW* in Ref. 1.

^{a)}Electronic mail: zfliu@wayne.edu

ACKNOWLEDGMENTS

Z.-F.L. acknowledges support from NSF CAREER Award No. DMR-2044552. This work used Bridges-2 at Pittsburgh Supercomputing Center through allocation PHY220043 from the Advanced Cyberinfrastructure Coordination Ecosystem: Services & Support (ACCESS) program, which is supported by NSF grants #2138259, #2138286, #2138307, #2137603, and #2138296. Additionally, large-scale *GW* calculations were performed using resources of the National Energy Research Scientific Computing Center, a DOE Office of Science User Facility supported by the Office of Science of the U.S. Department of Energy under Contract No. DE-AC02-05CH11231 using NERSC award BES-ERCAP0027306.

¹O. Adeniran and Z.-F. Liu, “Quasiparticle electronic structure of phthalocyanine:TMD interfaces from first-principles *GW*,” J. Chem. Phys. **155**, 214702 (2021).

²M. Drüppel, T. Deilmann, P. Krüger, and M. Rohlfing, “Diversity of trion states and substrate effects in the optical properties of an MoS₂ monolayer,” Nat. Commun. **8**, 2117 (2017).

³M. H. Naik and M. Jain, “Substrate screening effects on the quasiparticle band gap and defect charge transition levels in MoS₂,” Phys. Rev. Mater. **2**, 084002 (2018).

⁴N. Zibouche, M. Schlipf, and F. Giustino, “*GW* band structure of monolayer MoS₂ using the Sternheimer*GW* method and effect of dielectric environment,” Phys. Rev. B **103**, 125401 (2021).